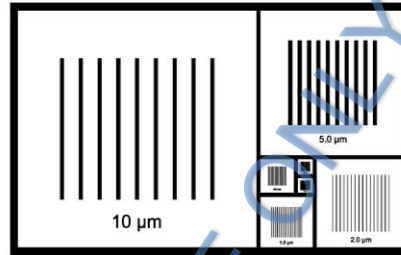
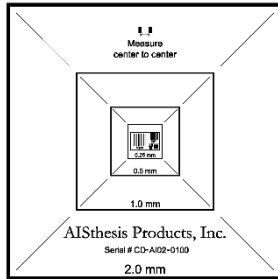


AISthesis Products

Advanced Imaging Products for Nanotechnology,
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PO Box 1950, Clyde NC 28721



Wafer Level Certificate of Traceability for Pelcotec™ Critical Dimension Magnification Standard



Product Number: **Pelcotec™** 692-01 CDMS-0.1T-ISO

Customer name and contact information:

Product Description: 2.5x2.5mm, **Pelcotec™** 2mm-100nm Critical Dimension Magnification Standard



Wafer Identifier: CD-AI02

P.O. Box 492477

As Received Condition: New

Redding, CA 96049-2477

As Returned Condition: N/A

Tel: 530.243.2200

Date of Receipt: N/A

www.tedpella.com

The accuracy of this product with Wafer Identifier CD-AI02 was determined using a Field Emission Scanning Electron Microscope (FE-SEM) by reference comparison to working standards traceable to the National Institute of Standards and Technology (NIST), using CP 01 FE-SEM Imaging of Critical Dimension Magnification Standards (CDMS) and CP 02 Certification of Critical Dimension Magnification Standards. Die were sampled according to method SOP 08 Sampling Die. The data applies only to the CDMS products identified in this report. All results are "as-is". Repair and/or adjustments are not possible.

Below are the average ISO 17025:2017-compliant Certified 10 μm Pitch Measurements unique to Die with Wafer Identifier CD-AI02 and traceable to NIST Certified Standard CD-PG01-0211.

Line	ISO 17025:2017 Compliant Certified Average Pitch on Wafer	Position of Measurement
0-10 μm	9.998 μm	± 7.5 μm from center
10-20 μm	10.000 μm	± 7.5 μm from center
20-30 μm	10.003 μm	± 7.5 μm from center
30-40 μm	10.000 μm	± 7.5 μm from center
40-50 μm	10.002 μm	± 7.5 μm from center
50-60 μm	9.999 μm	± 7.5 μm from center
60-70 μm	10.000 μm	± 7.5 μm from center

70-80 μm	9.998 μm	$\pm 7.5 \mu\text{m}$ from center
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Average	10.000 μm
2-Sigma *	0.0331 μm

* Corrected for sample size using the appropriate Student t-factor.

Measurements are reported with an uncertainty ($k=2$)** of $\pm 0.012 \mu\text{m}$. Statements of Conformity are not provided in this report. Review the results and verify that they meet the requirements for the intended use. Physical damage to or contamination of the CDMS occurring after calibration may invalidate the reported measurements. Use this product at $25^\circ\text{C} \pm 5^\circ\text{C}$ and at less than 80% RH.

** Reported uncertainties represent expanded uncertainties expressed at approximately the 95% confidence level using a coverage factor of $k = 2$. The reported expanded measurement uncertainty is stated as the standard measurement uncertainty multiplied by the coverage factor K such that the coverage probability corresponds to approximately 95%.

Line	Number of Lines	Position of Measurement	Non-ISO 17025:2017 Compliant Average Measured Distance (first to last line)	Average Pitch of Wafer
2.0 mm	2	$\pm 1.00\text{mm}$ from center	2.00 mm	2.00 mm
1.0 mm	2	$\pm 0.5\text{mm}$ from center	1.00 mm	1.00 mm
0.5 mm	2	$\pm 0.25\text{mm}$ from center	0.500 mm	0.500 mm
0.25 mm	2	$\pm 0.125\text{mm}$ from center	0.250 mm	0.250 mm
10 μm	9	$\pm 7.5 \mu\text{m}$ from center	80.00 μm	10.00 μm
5.0 μm	12	$\pm 20 \mu\text{m}$ from center	55.01 μm	5.00 μm
2.0 μm	16	$\pm 10 \mu\text{m}$ from center	30.04 μm	2.00 μm
1.0 μm	17	$\pm 5 \mu\text{m}$ from center	16.02 μm	1.00 μm
500 nm	20	$\pm 4 \mu\text{m}$ from center	9.52 μm	501.0 nm
250 nm	21	$\pm 2.5 \mu\text{m}$ from center	5.02 μm	250.8 nm
100 nm	52	$\pm 2.5 \mu\text{m}$ from center	5.12 μm	100.3 nm

The average pitch is derived from the stated length that was determined using measurements (taken center-to-center) over the stated number of lines (i.e., length divided by the number of lines minus one).

Date of Analysis: January 29th, 2023

Equipment used:

Instrument	Model	Serial #	Resolution	Repeatability	Temperature	Humidity	Ref.
FE-SEM	FEI Verios 460L	9922551	0.9nm	0.030%	$23.3 \pm 0.3 \text{ }^\circ\text{C}$	$42.5 \pm 1.5\%$	CD-PG01-0211

Location: Analytical Instrumentation Facility, NC State University, Raleigh NC 27695-7531.

Notes:

D.S. Finch
Certified by

Signature

H. Haehlen
Authorized by

Signature

January 29th, 2023
Date report issued.

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P.O. Box 1950, Clyde, North Carolina 28721 Tel: 828.627.6555 E-mail: CDMS@aistHesisproducts.com

End of report.

EXAMPLE CERTIFICATE ONLY